



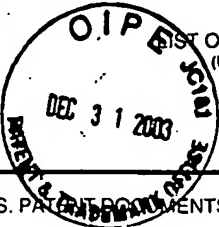



Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2271	SERIAL NO. 10/664,738	
<div style="text-align: center;">  </div> <div style="text-align: center;"> LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) </div>					APPLICANT: Micron Technology, Inc.		
					FILING DATE September 18, 2003	GROUP 1763	
U.S. PATENT DOCUMENTS							
*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
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		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AJ						
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM	✓	B. Garrido et al., "The Role of Chemical Species in the Passivation of <100> Silicon Surfaces by HF in Water-				
			Ethanol Solutions", J. Electrochem. Soc., Vol. 143, No. 12, December 1996, pp. 4059-4066.				
	AN	✓	Wood et al., "Etching Silicon Nitride and Silicon Oxide Using Ethylene Glycol / Hydrofluoric Acid Mixtures",				
			Electrochemical Society Proceedings Volume 99-36, pp. 258-263.				
	AO	✓	Knotter et al., "Etching Mechanism of Silicon Nitride in HF-Based Solutions", J. Electrochem. Soc., 148 (3),				
			2001, pp. F43-F46.				
EXAMINER		DATE CONSIDERED					
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							

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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM	<input checked="" type="checkbox"/>	T. Kezuka et al., "The Control of Etching Rate for Various SiO ₂ Films", Electrochemical Society Proceedings,				
			Vols. 99-36, 2000, pp. 244-251.				
	AN						
	AO						
EXAMINER		DATE CONSIDERED					
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